

What Is Claimed Is:

1. A method for producing micromechanical structures comprising:
  - depositing a functional layer onto a sacrificial layer;
  - removing the sacrificial layer again, for the production of at least one mechanical functional element; and
  - removing, at least to a considerable part, a surface barrier layer, with which the functional layer on the sacrificial layer begins, and which has a different state from a remaining functional layer.
2. The method according to claim 1, further comprising:
  - applying the functional layer in a composition of the surface barrier layer as seen in a direction of the remaining functional layer; and
  - etching at least one part of the surface barrier layer at least initially selective to at least one of the surface barrier layer and the remaining functional layer.
3. The method according to claim 2, further comprising:
  - depositing the functional layer, in at least one partial area of the surface barrier layer, all the way into the remaining functional layer, made of SiGe having a higher proportion of germanium than 65% to 70%, but less than 100%; and
  - reducing the germanium proportion during the depositing for the remaining functional layer, to a proportion of less than 65% to 70%.
4. The method according to claim 1, further comprising applying the functional layer completely in a composition which demonstrates no, or only a weak selectivity for the sacrificial layer.
5. The method according to claim 1, further comprising applying to the functional layer at least one layer having at least approximately the same properties with respect to a stress in the at least one layer, with which the functional layer begins on the sacrificial layer and which has a different state from the remaining

functional layer.

6. The method according to claim 5, wherein the at least one layer includes the surface barrier layer.

7. A micromechanical structure comprising:

a functional layer composed of SiGe;

a remaining structure; and

a lateral region separating the functional layer from the remaining structure,

wherein the functional layer, as seen over its thickness, has a construction so that one of (a) stresses in the functional layer are neutralized, at least for the most part, and (b) no stress gradient appears.

8. The structure according to claim 7, wherein the functional layer, as seen over its thickness, is constructed at least approximately symmetrically to a center plane through the functional layer.

9. The method according to claim 7, further comprising a remaining functional layer, and wherein the functional layer in each case has a surface barrier layer on opposite surfaces, which differs from the remaining functional layer.

10. The method according to claim 7, wherein the functional layer is at least approximately homogeneous, as seen over its cross section.